

DC/RF-Magnetron Sputter equipment

Description of facility

The magnetron sputtering equipment LA 250S (vonArdenne Anlagentechnik) can be operated with two separate sources at DC or RF power supply. Sputter etching, BIAS voltage, use of three different gases, total pressure measurement and plasma-emission-monitoring are possible. Manufacture of metallic or ceramic coatings in monolithic, graded, or multilayer arrangement up to several μm in thickness is achievable. Sample rotation and planetary drives allow coating of several samples in one batch. The maximum target diameter used is 90mm.

Application

- Manufacture of metallic or ceramic coatings
- Coating of several samples in one batch

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This handout, and cross-references to related measurement techniques and facilities are available at: <http://messtec.dlr.de/link-284-en>.

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